

Abstract Submitted
for the MAR15 Meeting of
The American Physical Society

Network structures of triblock copolymer by two-step phase separation MIKIHITO TAKENAKA, Kyoto University, RIKEN, AYANO INOUE, HIROKAZU HASEGAWA, Kyoto University — We investigated network structures of polystyrene-*b*-polyisoprene-polydimethylsiloxane (PS-PI-PDMS) triblock copolymer formed solvent cast processes. The obtained morphologies were observed by 3D-TEM and SAXS. Two-step phase transition occurs during the self-assembling processes of PS-PI-PDMS in solvent cast processes, resulting in the morphologies such as OBDD and P-surface, which is not formed in the equilibrium state of triblock copolymer.

Mikihito Takenaka
Kyoto University

Date submitted: 14 Nov 2014

Electronic form version 1.4